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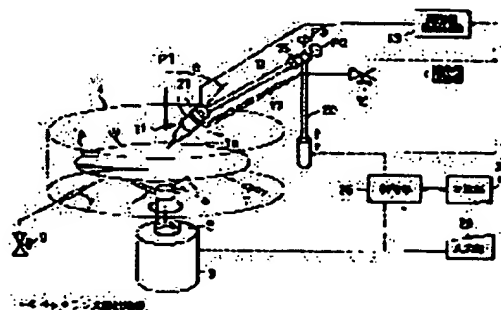
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(54) METHOD OF WASHING SUBSTRATE AND DEVICE THEREFOR

(57)Abstract:

PROBLEM TO BE SOLVED: To restrain ultrasonic damage to one surface of a substrate while covering its other surface with a liquid film to prevent particles from being restock.

SOLUTION: In a method of washing a substrate in which washing liquid with ultrasonic waves is fed from a nozzle 11 to the rear of a substrate W whose surface is covered with a liquid film to wash it, washing is performed under the condition to satisfy $1 < ft < 5$ and $34 < ? < 70$ where the frequency of the ultrasonic waves, the thickness of the substrate W, and the incident angle of the washing liquid with the normal of the surface of the substrate W as a reference are defined as f [MHz], t [mm], and ? [°] respectively. For example, if the substrate W of 300 mm diameter (thickness t=0.775 [mm]) is washed when the frequency f=3 [MHz] and the incident angle ?=35[°], the above condition is satisfied and the permeability of the ultrasonic waves to the surface of the substrate W can be restrained than before to restrain ultrasonic damage.



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